	Hits	Search Text	DBs
38	28	((resist or photoresist)) and (resin$4 same (polyvinyl near16 (aryl or benzyl or phenyl) near15 (acetal or ether or ester))) and (surfactant same (cationic or anionic or amphoteric))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
39	7	((resist or photoresist) same pattern) and (resin$4 same (polyvinyl near16 (aryl or benzyl or phenyl) near22 (acetal or ether or ester))) and (resin same surfactant same (cationic or anionic or amphoteric))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
40	145	((resist or photoresist)) and (resin$4 same (water$5soluble) same (thicken$5 or enhanc$4 or smooth$6 or shrinking)) and (surfactant same (cationic or anionic or amphoteric))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
41	122	S40 NOT S38	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB